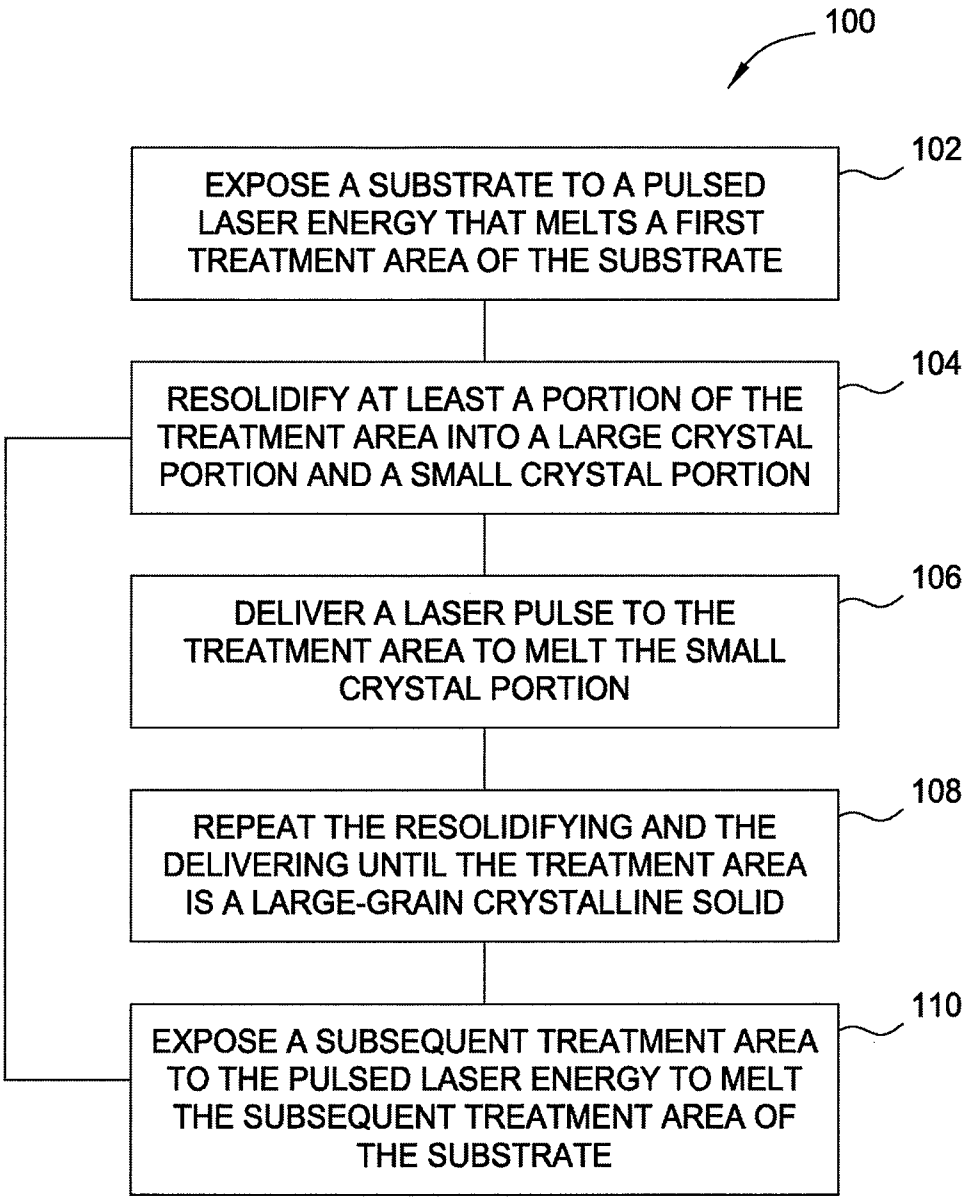

100
EXPOSE A SUBSTRATE TO A PULSED LASER ENERGY THAT MELTS A FIRST TREATMENT AREA OF THE SUBSTRATE
102
RESOLIDIFY AT LEAST A PORTION OF THE TREATMENT AREA INTO A LARGE CRYSTAL PORTION AND A SMALL CRYSTAL PORTION
104
DELIVER A LASER PULSE TO THE TREATMENT AREA TO MELT THE SMALL CRYSTAL PORTION
106
REPEAT THE RESOLIDIFYING AND THE DELIVERING UNTIL THE TREATMENT AREA IS A LARGE-GRAIN CRYSTALLINE SOLID
108
EXPOSE A SUBSEQUENT TREATMENT AREA TO THE PULSED LASER ENERGY TO MELT THE SUBSEQUENT TREATMENT AREA OF THE SUBSTRATE
110

FIG. 1

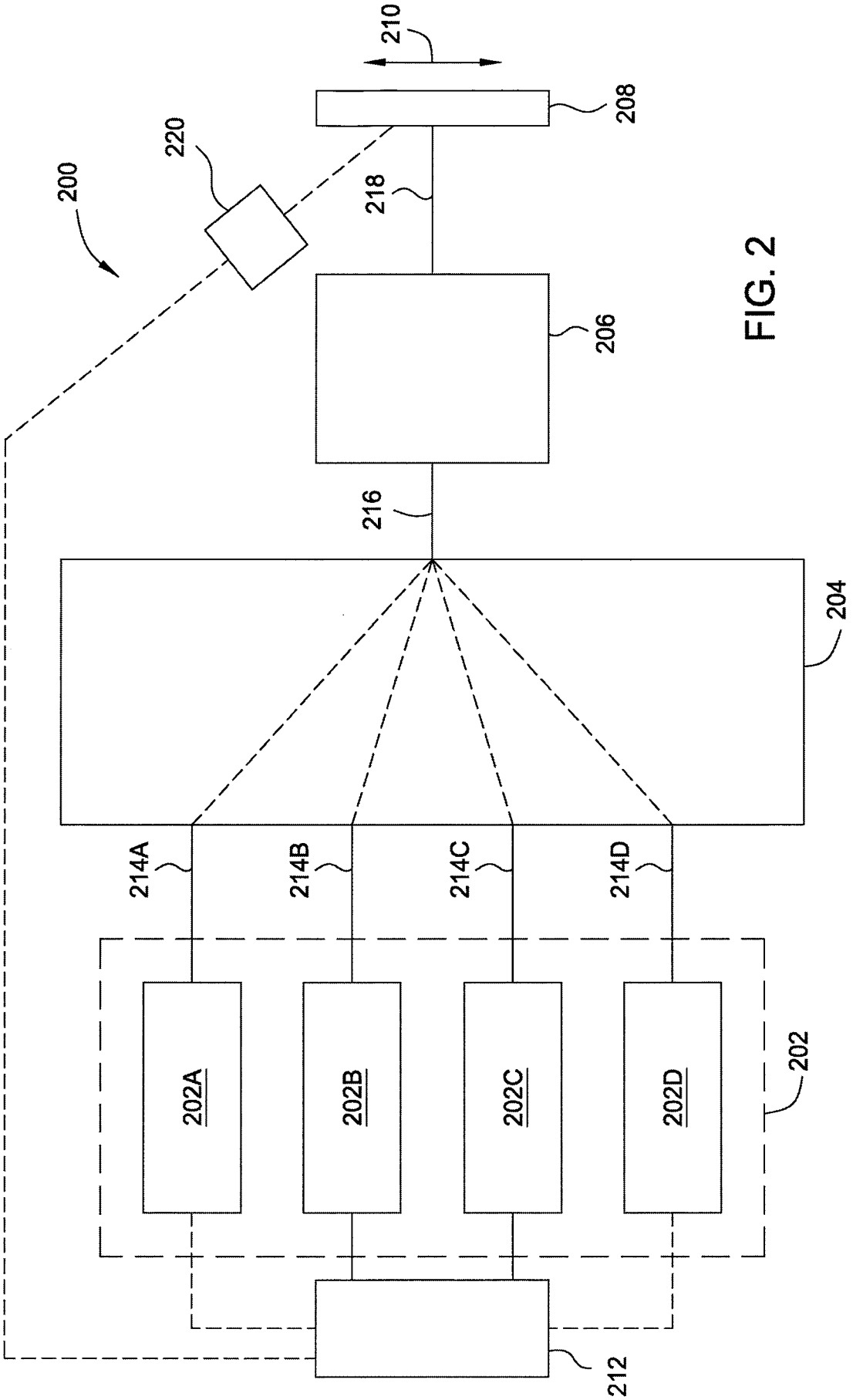

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FIG. 2